# A simple model and parameter extraction method for the description of ON-current of LT-PS TFT

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#### **Abstract**

A simple SPICE model for the description of the on-current of low-temperature poly-silicon thin film transistors is proposed. By employing constant mobility,  $V_{\rm GS}$  dependent alpha parameter, and exponential kink effect, very good agreements between the model and measurement were obtained.

## 1. Introduction

Low Temperature Poly-Silicon (LT-PS) Thin Film Transistors (TFTs) are expected to play an important role in the next generation flat-panel display technology[1]. In order to use the LT-PS TFTs in semiconductor circuits, an accurate modeling of device characteristics is essential. The most widely used model of LT-PS TFTs are by Jacunski et al which is implemented as HSPICE MOSFET Level 62 (or AIM-SPICE Level 16) [2,3]. Although this model is quite accurate, at least for the description of the DC characteristics, the parameter extraction for this model is quite involved.

In this paper, we propose a very simple analytical model to describe the ON-current behavior of LT-PS TFTs and the parameter extraction technique for the model. By employing  $V_{GS}$ -dependent  $\alpha$ -parameter, and exponential kink effect, very good agreements between the model and measurement were obtained for the ON-current behavior of short channel devices, where channel length is as short as  $4 \ \mu m$ .

### 2. Results

Above threshold, the drain current in the linear region of poly-silicon TFT can be expressed as

$$I_a = \mu C_{ox} \frac{W}{L} \left[ (V_{GS} - V_T) V_{DS} - \frac{V_{DS}^2}{2\alpha} \right], \quad (1)$$

where  $\mu$  is the carrier mobility,  $C_{ox} = \varepsilon_{ox}/t_{ox}$  is the gate-oxide capacitance per unit area, where  $\varepsilon_{ox}$  is the dielectric permittivity and  $t_{ox}$  is the thickness of the gate oxide. W and L are the channel width and length, respectively.  $V_{GS}$  and  $V_T$  are gate-source voltage and the threshold voltage, respectively.  $\alpha$  is the body-effect related parameter.

If we assume that  $\alpha$ ,  $\mu$  and  $V_T$  in Eq. (1) are independent of  $V_{DS}$ , we can fit the measured  $I_{DS}$  ( $V_{DS}$ ) to the quadratic function of Eq. (2)

$$I_{DS} = AV_{DS} - BV_{DS}^{2}.$$
 (2)

when compare Eqs (1) and (2), we can establish following relationship.

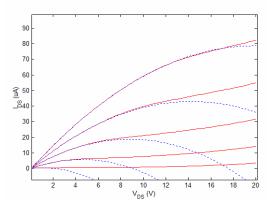
$$A = \mu C_{ox} \frac{W}{L} (V_{GS} - V_T), \qquad (3a)$$

$$B = \mu C_{ox} \frac{W}{L} \frac{1}{2\alpha}, \tag{3b}$$

$$\frac{A}{B} = 2\alpha (V_{GS} - V_T). \tag{3c}$$

Figure 1 shows the result of the quadratic fitting. We observe that the fitting is very good for small  $V_{DS}$ . As the device goes into saturation

with large  $V_{\rm DS}$ , the quadratic curves diverge from the measured curves.



**Figure 1.** Comparison of the  $I_D - V_{DS}$  curves by measurement (solid) and quadratic fitting curve (dotted)

Fig. 2 shows the parameters A and B in Eq. (2) extracted for Fig. 1. From Fig. 2 (a), we can observe that  $A(V_{GS})$  is almost straight line. This implies that the carrier mobility can be considered to be a constant for this device. We can extract this constant mobility  $\mu$  from the slope of the line and  $V_T$  from the intercept of this line with the  $V_{GS}$ -axis. Next, from Fig. 2 (b), we can observe that  $\alpha$  is a strong function of  $V_{GS}$ . This is illustrated again in Fig. 2 (c) where  $\alpha = (A/2B)/(V_{GS} - V_T)$  is shown (solid line). We can fit  $\alpha$  to a quadratic function of  $V_{GS}$  as shown in Fig. 2 (c) (dotted line).

In the saturation region, the drain current can be described as,

$$I_{DS} = \alpha \cdot \frac{1}{2} \mu C_{ox} \frac{W}{L} (V_{GS} - V_T)^2$$
. (4)

The Eqs (1) and (3) can be combined into one equation as follows[4],

$$I_{DS} = \mu C_{ox} \frac{W}{L} \left[ (V_{GS} - V_T) V_{DSe} - \frac{V_{DSe}^2}{2\alpha} \right], \quad (5)$$

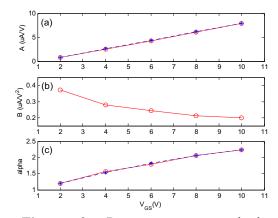
where  $V_{DSe}$  is effective intrinsic drain-source voltage defined as [5,6]

$$V_{DSe} = \frac{V_{DS}}{\left[1 + \left(\frac{V_{DS}}{V_{sat}}\right)^{M_{SS}}\right]^{\frac{1}{M_{SS}}}},\tag{6}$$

where  $V_{sat}$  is above-threshold saturation voltage given as [7],

$$V_{sat} = 2^{\frac{1}{M_{SS}}} \cdot \alpha \cdot V_{GT}, \qquad (7)$$

and  $M_{SS}$  is the fitting parameter which controls the transition between the triode region and the saturation region. For long-channel devices, we typically have  $M_{SS} >> 1$  in which case  $V_{sat} \approx \alpha \cdot V_{GT}$ .

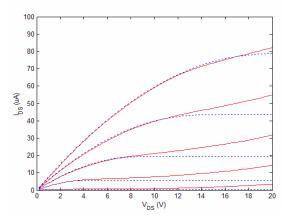


**Figure 2.** Parameters extracted by parabolic fitting to the linear region I - V curves. (a) A (solid: measurement, dotted: linear fit) (b) B (c)  $\alpha = (A/2B)/(V_{GS} - V_T)$  (solid: measurement, dotted: quadratic fit)

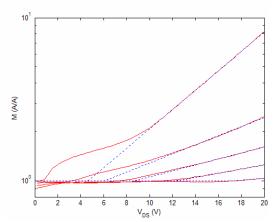
Figure 3 shows modeled  $I_{DS} - V_{DS}$  curves which calculated with takes the saturation effect into consideration[3]. We can observe that the agreement between the measurement (solid line) and the model (dotted line) is quite good in the

linear region. However, for large  $V_{\rm DS}$  , the agreement betweens poor. This is due to kink effect.

We define multiplication factor M due to kink effect as the ratio of measured  $I_{DS}$  to the calculated  $I_{DS}$  not including the kink effect.



**Figure 3.** Comparison of the  $I_D - V_{DS}$  curves by measurement (solid) and the modeling not including the kink effect (dotted)



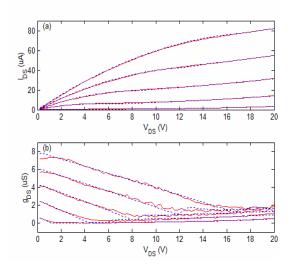
**Figure 4.** Current multiplication factor M defined as the ratio of measured  $I_{DS}$  to the modeled  $I_{DS}$  not including the kink effect (solid). Dotted lines represent exponential fit in the large  $V_{DS}$  region.

Figure 4 shows the multiplication factor M obtained from the  $I_{DS}$  curves in Fig. 3. We can observe that M is a strong function of both  $V_{GS}$  and  $V_{DS}$ , and for large values of  $V_{DS}$ , M can be modeled as

$$M = C \exp(D \cdot V_{DS}), \qquad (8)$$

where C and D are functions of  $V_{GS}$ . The dotted lines in Fig. 4 represent the result of this exponential function fitting.

Figure 5 (a) compares the  $I_{DS}$  curves calculated using the above kink effect model with the measured curves. We can observe excellent agreements between the curves. Fig. 5 (b) shows the output conductance of the TFT defined as  $g_{DS} = \partial I_{DS} / \partial V_{DS}$ . The output resistances obtained by numerically differentiating the measured data and modeled one agree very well both in the linear region and the saturation region.



**Figure 5**. (a) Comparison of  $I_D - V_{DS}$  curves from measurement (solid) and modeling (dotted) (b) Output resistance by numerically differentiating the  $I_D - V_{DS}$  curves from the measurement (solid) and modeling (dotted)

#### 3. Conclusions

In conclusion, we proposed a very simple model for the description of on-current behavior of LT-PS TFTs. The parameter extraction technique is very straightforward and does not involve any nonlinear optimization. By employing constant mobility,  $V_{GS}$  dependent  $\alpha$  - parameter, and exponential kink effect, a very good agreement between the model and measurement was obtained.

## 4. Acknowledgements

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